A-2 Plasma Deposition

Representative Organizer

Naho ITAGAKI (Kyushu University)

Co-organizers

Makoto KAMBARA (The University of Tokyo)

Song-Yun KANG (Tokyo Electron Limited)

Hisao MAKINO (Kochi University of Technology)

Oral Session March 30 (Mon.) Room 1

Chair: Makoto Kambara (The University of Tokyo)

8:50 A2-I-01 An Elastic Effect in Crystal Growth: Change of Growth Modes with Dislocations in Heteroepitaxy [Invited Lecture]

¹Hiroyasu Katsuno, ²Makio Uwaha

1 DEPARTMENT OF PHYSICAL SCIENCES, RITSUMEIKAN UNIVERSITY

2 DEPARTMENT OF PHYSICS, NAGOYA UNIVERSITY

9:20 A2-I-02 Growing Demand for Plasma-Enhanced ALD in Sub-20 nm Semiconductor Manufacturing

Nobuyoshi Kobayashi *ASM JAPAN K.K.*

9:50 A2-O-01 Effects of Gas Flow Rate on Deposition Rate and Amount of Si Clusters Incorporated into a-Si:H Films

Susumu Toko, Yoshihiro Torigoe, Kimitaka Keya, Hyunwoong Seo, Naho Itagaki, Kazunori Koga, Masaharu Shiratani KYUSHU UNIVERSITY

10:05 A2-O-02 Constructing the Nano-Au Quasi-Mesh Structures to Enhance the Conductivity of Al-Doped ZnO Thin Films

Cheng-Wei Chen, Yen-Sheng Lin

DEPARTMENT OF ELECTRONIC ENGINEERING, I-SHOU UNIVERSITY

10:20 A2-O-03 Low-Temperature Synthesis of Carbon Nanotubes on Nanoporous Templates Using Plasma-Assisted Hybrid Chemical Vapor Deposition System

Eun-Hye Kwak, Goo-Hwan Jeong

DEPARTMENT OF NANO APPLIED ENGINEERING, KANGWON NATIONAL UNIVERSITY

10:35 A2-O-04 Dependence of VHF Power on Electronic Properties of Amorphous Carbon Films Grown by Plasma-Enhanced Chemical Vapor Deposition

<u>Hirotsugu Sugiura</u>, Lingyun Jia, Da Xu, Masayuki Nakamura, Keigo Takeda, Kenji Ishikawa, Hiroki Kondo, Makoto Sekine. Masaru Hori

GRADUATE SCHOOL OF ENGINEERING, NAGOYA UNIVERSITY

10:50 A2-O-05 Effects of Ion Irradiation on Mass Density of Carbon Films Deposited by H-Assisted Plasma CVD

Xiao Dong, Kazunori Koga, Daisuke Yamashita, Hyunwoong Seo, Naho Itagaki, Masaharu Shiratani GRADUATE SCHOOL OF INFORMATION SCIENCE AND ELECTRICAL ENGINEERING, KYUSHU UNIVERSITY